Silicon in Synthesis. Methoxymethyltrimethylsilane, a New Reagent for Reductive Nucleophilic Acylation

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Summary Lithium methoxy(trimethylsilyl)methylide (6), prepared by deprotonation of methoxymethyltrimethylsilane (3) using s-butyl-lithium reacts with ketones and aldehydes to give adducts (7b)—(9b) that can be converted into aldehydes.

RECENTLY we described the use of α -chloromethyl(trimethyl)silane (1) for reductive nucleophilic acylations (Scheme).¹ The use of s-butyl-lithium for the formation



of the α -lithio species (2) from (1) is essential, and we have not yet discovered any other base that will accomplish this deprotonation so specifically. It was of particular interest to us that reported attempts to deprotonate methoxymethyl(trimethyl)silane (3) using n-butyl-lithium resulted in nucleophilic attack at silicon and subsequent cleavage of the $-CH_2OMe$ group; t-butyl-lithium gave the α -lithiospecies (4), which could be regarded as a kinetic product.² Furthermore it has been reported that $\alpha\beta$ -epoxysilanes are opened with MeOH-BF₃·Et₂O or MeOH-CF₃CO₂H to give



exclusively the α -methoxy-adduct (5).³ The adduct (5) would result from the nucleophilic addition of the α -lithiospecies (6) to an aldehyde or ketone.

Treatment of methoxymethyltrimethylsilane $(3)^4$ in tetrahydrofuran (THF) with s-butyl-lithium (1.4M in hexane) at -70 °C followed by warming to -25 °C gave the lithium methoxy(trimethylsilyl)methylide (6), as judged by



its subsequent reactions with aldehydes and ketones (7a)-(9a). The initial adducts (7b)-(9b) did not undergo synelimination of -OSiMe₃ in situ, but upon treatment with KH in THF at 25 °C the corresponding enol ethers (7c)-(9c) were formed in excellent yields.[†] Treatment of the adducts (7b)-(9b) with 90% aqueous formic acid gave the aldehydes (7d)—(9d) in > 90% yields. Previously (8d) had been reported as an unstable compound;⁵ using the new procedure described here (8d) was isolated as a stable crystalline compound, m.p. 99-102 °C. We were unable to hydrolyse the adduct (10b) with formic acid without causing extensive degradation. When the adducts (7b)---(9b) were treated with caesium fluoride in dimethyl sulphoxide at 80 °C with the objective of eliminating HOSiMe₃ under essentially neutral conditions, surprisingly the -SiMe₃ group was cleanly removed to give the desilylated adducts (7e)—(9e), with no trace of the enol ethers (7c)—(9c). The adduct (9b) was rapidly oxidized with pyridinium chlorochromate⁶ to give (7f), chromatography of which on silica gel effected desilylation to give (7g).

The reagent methoxymethyltrimethylsilane (3) provides a new procedure for conducting reductive nucleophilic acylations and a source of the -CH₂OMe anion.⁷

All new compounds gave satisfactory spectral data.

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† It should be noted that Peterson olefinations conducted with Me₃SiCHLiSMe under similar conditions to those reported here provide directly the vinyl sulphide through the in situ syn-elimination of -OSiMe₃ (ref. 2).

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